Declaration of Vacuum Pump Contamination

Pumps International, Inc.

161 N Gibson Rd Henderson NV 89014 Contact: Betsy Stanton Phone: 702-565-9384

Email Address: Bbrogan@garlic.com Website: http://www.pumpsint.com

ADDRESS ALL SHIPMENTS-ATTN: BETSY STANTON

Complete this form before sending any pumps to Pumps International, Inc. (PI) for repair. Fax and or email the completed form to PI and include a copy with each unit

Company:		Date: Email:		
Contact:	Phone#:	Email:		
Address:				
City:	State:	Zip:		
Manufacturer.	Model:			
PO#:	S/N:			
Reason for pump bein	g returned, please be spe	cific:		
If Turbo, cooled by: A	Air Water			
If applicable check oil	type to return in unit:	PFPEHydrocarbon		
		cautions when handling contaminated		
		s of damaging & dangerous contaminants, but		
does not eliminate the				
		stance if you have any questions.		
	•	istry: (Please respond to each item!)		
Air (if no chemistry, c		Nitrogen (N2)		
Ammonia (NH3)	neek nere)	Nitrogen (N2) Nitrogen Triflouride (NF3)		
Argon (Ar)		Nitrous Oxide (N2O)		
Arsenic (As		Oxygen (O2)		
Arsine (AsH3)		Ozone (O3)		
Boron Trichloride (BC	C13)	Phosphine (PH3)		
Boron Trifluoride (BF		Silane (SIH4)		
Carbon Tetrachloride		Sulfur Hexaflouride (SF6)		
Carbon Tetrafluoride		Tetraethylorthosilicate (C2H2o4Si) (TEOS)		
Chlorine (Cl2)	,	Tetrafluoromethane (CF4) (Freon 14)		
Dichlorosilane (SlH20	Cl2) (DCS)	Trifluoromethane (CHF3) (Freon 23)		
Hexafluoroethane (C2	F6) (Freon 116	Trimethylboron (B (CH3)3)		
Hydrogen Bromide (H	(Br)	Trimethylphosphite (C3HSO3P) (TMP)		
Hydrochloric Acid (H		Tungsten Hexaflouride (WF6)		
Hydroflouric Acid (H	F)			
Write in Chemicals if not l	isted: (Chemicals not listed sh	nould include CAS #)		
*Attach MSDS sheets, if a	vailable, to pump			

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Declaration of Vacuum Pump Contamination (cont.)

Unit has been exposed to the following: (Please respond to all that apply!) Non-hazardous Flammable Equipment & components which have been Biological hazard Toxic contaminated by biological, explosive, or Radioactive Explosive radioactive substances will not be accepted Carcinogenic Corrosive without written evidence of decontamination						
For Semiconductor only Implantation: Etch: Polysilicone:	y: Process/Tool Deposition:	Information PVD: Deep:	TEOS-CVD:Trench: Silicide:	MCVD: Oxide:		
Additional Comments:						
End User Signature:			Date:			